

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)	Docket Number (Optional) TWI-13310	Application Number 10/053,373
	Applicant(s) Jeffrey T. Fanton et al.	
	Filing Date October 24, 2001	Group Art Unit Unknown

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
JK	AA	5,042,951	08/27/1991	Gold et al.	356	369	09/19/1989
JK	AB	5,412,473	05/02/1995	Rosencwaig et al.	356	351	07/16/1993
JK	AC	5,619,548	04/08/1997	Koppel	378	70	08/11/1995

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
JK	AD	WO 92/08104	05/14/1992	PCT	G01B	11/24		
JK	AE	WO 00/57127	09/28/2000	PCT	G01B	11/06		
JK	AF	WO 01/71325	09/27/2001	PCT	G01N	23/00		

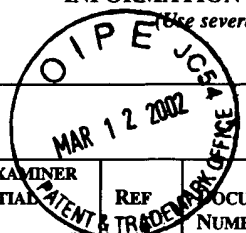
OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

JK	AG	K. Sakurai et al., "Fourier Analysis of Interference Structure in X-Ray Specular Reflection from Thin Films," <i>Jpn. J. Appl. Phys.</i> , Vol. 31, Part 2, No. 2A, 1 February 1992, pp. L113-L115.
JK	AH	K.N. Stoev et al., "Review on grazing incidence X-ray spectrometry and reflectometry," <i>Spectrochimica Acta Part B</i> , Vol. 54, 1999, pp. 41-82.
JK	AI	N. Wainfan et al., "Density Measurements of Some Thin Copper Films," <i>Journal of Applied Physics</i> , Vol. 30, No. 10, October 1959, pp. 1604-1609.
JK	AJ	J.P. Sauro et al., "Some Observations on the Interference Fringes Formed by X Rays Scattered from Thin Films," <i>Physical Review</i> , Vol. 143, No. 1, March 1966, pp. 439-443.
JK	AK	K. Sakurai et al., "Analysis of thin films by X-ray scattering at grazing incidence," <i>Spring-8 User Experiment Report No. 2 (1998 A)</i> , March 1999, p. 162.
JK	AL	J.M. Grimal et al., "X-ray reflectivity: a new tool for the study of glass surfaces," <i>Journal of Non-Crystalline Solids</i> , Vol. 196, 1996, pp. 128-133.
JK	AM	P. Polouček et al., "X-ray reflectivity analysis of thin complex Langmuir-Blodgett films," <i>Journal of Physics D: Applied Physics</i> , Vol. 34, 2001, pp. 450-458.
JK	AN	C.E. Bouldin et al., "Thermal expansion coefficients of low-k dielectric films from Fourier analysis of x-ray reflectivity," <i>Journal of Applied Physics</i> , Vol. 88, No. 2, 15 July 2000, pp. 691-695.
JK	AO	Wen-Li Wu et al., "Study of ultra-thin hydrogen silsesquioxane films using X-ray reflectivity," <i>Thin Solid Films</i> , Vol. 312, 1998, pp. 73-77.
JK	AP	E.K. Lin et al., "Structure and Property Characterization of Porous Low-k Dielectric Constant Thin Films using X-ray Reflectivity and Small Angle Neutron Scattering," <i>Mat. Res. Soc. Symp. Proc.</i> , Vol. 612, 2000 [Materials Research Society], pp. D4.1.1-D4.1.8.
JK	AQ	B.J. Bauer et al., "Structure and Property Characterization of Low-k Dielectric Porous Thin Films," <i>Electronics Materials</i> 30(4), pp. 304-308, 2001.
JK	AR	P. Boher et al., "Radio frequency sputtering of tungsten/tungsten nitride multilayers of GaAs," <i>J. Vac. Sci. Technol. A</i> , Vol. 8, No. 2, Mar/Apr 1990, pp. 846-849.
JK	AS	E. Chason et al., "In situ energy dispersive x-ray reflectivity measurements of H ion bombardment on SiO ₂ /Si and Si," <i>Appl. Phys. Lett.</i> , Vol. 60, No. 19, 11 May 1992, pp. 2353-2355.

Examiner <i>Frank E. Knadze</i>	Date Considered <i>07/07/03</i>
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

IK	AT	N. Awaji et al., "High-Accuracy X-ray Reflectivity Study of Native Oxide Formed in Chemical Treatment," <i>Jpn. J. Appl. Phys.</i> , Vol. 34, 1995, pp. L1013-L1016.
IK	AU	W.C. Johnson et al., "Rapid X-Ray reflectometry (XRR) metrology applied to Cu/low-k Damascene process development," <i>In Process Control and Diagnostics, Proceedings of SPIE</i> , Vol. 4182, 2000, pp. 106-114.
IK	AV	B. Poumellec et al., "A new method to extract the X-ray absorption fine structures from the reflectivity spectra: application to the study of (Ti.Nb)O ₂ amorphous solid solutions," <i>Physica B</i> , Vol. 158, 1989, pp. 282-283..

Examiner Shahli K. Kade	Date Considered 07/07/03
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	